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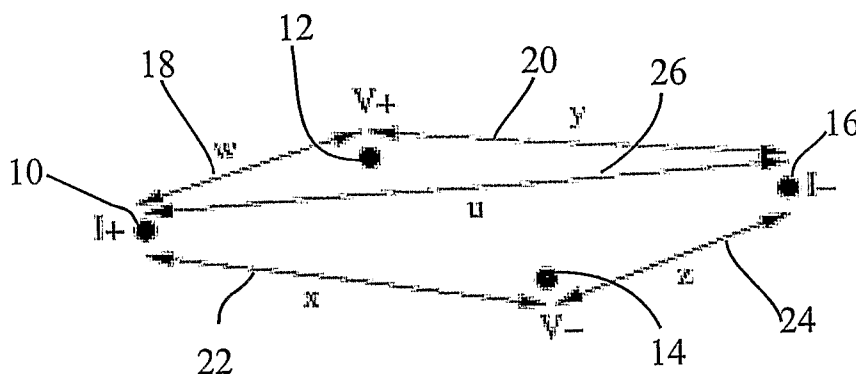
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(54) Title: ELIMINATING INLINE POSITIONAL ERRORS FOR FOUR-POINT RESISTANCE MEASUREMENT



(57) Abstract: The present invention relates to a method for calculating a correction factor for reduction of positional errors in resistance measurements using four-point probes. The four-point probe has a body and four probe arms each including a probe, the probe arms extending parallel from the body. The four-point probe includes electrical contact points for establishing electrical contact between the probes and a test apparatus transmitting and receiving electrical signals. The

method may comprise the steps of positioning the probe arms in contact with a surface of the test sample, selecting a first set comprising a first and a second probe arm and a second set comprising a third and a fourth probe arm, and applying a first current from the test apparatus through the first probe arm of the first set to the second probe arm of the first set, the first current propagating through the test sample, detecting a first induced voltage between the third and probe arms of the second set, and calculating a first four-point resistance, R_{first} , being a ratio of the first voltage and the first current. Furthermore, the method may comprise selecting a third set comprising a first and a second probe arm, wherein the third set includes no more than one of the probe arms of the first set, and a fourth set comprising a third and a fourth probe arm wherein the fourth set includes no more than one of the probe arms of the second set, applying a second current from the test apparatus through the first probe arm of the third set to the second probe arm of the third set, the second current propagating through the test sample, detecting a second induced voltage at the third and probe arms of the fourth set, and calculating a second four-point resistance, R_{second} , being a ratio of the second voltage and the second current. Still further, the method may comprise calculating a correction factor based on the first and second four-point resistance.